

**Influence of the Precursors and Chemical Composition of
the Solution on the Properties of ZnO Thin Films Grown by
Spray Pyrolysis**

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Abstract

The effect of the solution composition on the properties of ZnO thin films grown by spray pyrolysis has been investigated. The ZnO films, both undoped and doped with either magnesium or aluminium, have been grown employing different solvents and different precursor salts. Afterwards the effects of these have been correlated to the morphology, optical and electrical properties of the films. In general it was found that organic salts are preferable over inorganic ones such as chlorides and nitrates. In the case of inorganic salts, unwanted etching processes, caused by acids formed as a result of the precursor decomposition lead to degradation of the films performance. Similarly, organic solvents are preferable over water due to a better droplet size distribution and, also, due to additional heat transfer towards the sample surface by their burning.

Keywords: doped zinc oxide, transparent conductive oxide, spray pyrolysis, resistivity, morphology ZnO:Al

Introduction

Spray pyrolysis is an inexpensive, versatile growth technique for thin films with a wide range of application spreading from solar cells technology (anti-reflective coatings, transparent conducting oxides (TCO) and absorber layers (CIS, CIS2))¹⁻⁵ to gas sensors⁶, anodes for lithium-ion batteries⁷, optoelectronics devices⁵, as well as application in the glass industry⁸. Briefly, the spray-pyrolytic process consists of nebulizing a solution, containing the precursor salts, and transport towards a hot substrate by means of a gas stream^{1,9,10}. Within the hot zone above the substrate, the precursors undergo a pyrolytic decomposition, i.e. the thermal decomposition of the compound in the presence of oxygen¹¹, and a thin layer is deposited onto the substrate.

Key parameters of this process are: the atomization technique, aerosol transport (carrier gas, pressure, distance and reactor geometry), substrate temperature and material, and most importantly, the chemical composition of the solution^{1,5}.

Many efforts have been devoted to improve the performance of the nebulizing mechanism and different types of nozzles are commercially available today.^{1,12-15}. The crucial point is to get a homogeneous droplet size distribution as well as a small value for the mean particle size since better film quality is achievable in this case.^{1,16}

The carrier gas determines the oxidizing potency of the atmosphere in which the pyrolytic reaction takes place^{5, 17}, hence influencing the cation oxidation number in the final product. Moreover, pressure in the nozzle determines the rate at which the droplets reach the surface, thus influencing both the growth rate and the cooling rate of the surface^{5, 18}. In case of the blast nozzle the pressure and gas type also determines the droplet size

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3 distribution. Hence it has a more direct influence in the final film properties.
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6 The temperature of the substrate influences many different process parameters: aerosol
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8 transport towards the substrate, solvent evaporation, possibility of droplets impacting the
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10 surface and the dynamics of their spreading, and most importantly the precursor
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12 decomposition pathway ^{1,19}. Therefore, the surface temperature plays a major role in
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14 defining morphology and composition of the deposited film. In fact, by varying the
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16 temperature it is possible to change from regimes in which the precursor salts do not
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18 decompose to regimes associated with different oxidizing states possible for the precursor
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20 ²⁰. The importance of the substrate material is mainly related to its heat capacity.
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22 Materials with a low heat capacity and conductivity are cooled much faster by the spray
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24 than those that have large ones. This influences the performance of the overall process
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26 and changes effective growth temperatures ^{21,22}. For all parameters discussed so far, there
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28 is a clear understanding of their role and, even if their refinement for each individual
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30 system has to be done experimentally, the trend and generic influence has been confirmed
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32 in many cases. Although some attempts have been made, ²³⁻²⁵, the influence of the
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34 chemistry of the precursor solution has been less rigorously discussed. Only few general
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36 guidelines have been established. In particular it is known that solvents with lower
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38 density and surface tension (such as the alcohol-based ones) enable creating droplets of
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40 smaller size. Moreover solvents with lower boiling point vaporize easily and this can
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42 have a major consequence for achieving real pyrolytic decomposition ^{15, 18}. Furthermore,
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44 a co-solvent can be added in order to tune the oxidizing potency of the atmosphere where
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46 the reaction takes place ²⁰. Highly soluble precursors are preferred, as well as volatile
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48 molecules are required as co-product of the pyrolytic decomposition ^{9, 23}
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4 In the present article, the main role of each chemical component of the solution has
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6 been studied for both solvents and salt precursors. Undoped as well as Mg and Al doped
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8 ZnO has been investigated as a prototype system, mainly due to the easy availability of
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10 different precursor salts and their high solubility in different solvents. For each salt a
11
12 systematic variation of the temperature has been performed in order to find the most
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14 suitable growth temperature. Each precursor has been tested in a variety of solvents and,
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16 afterwards, a comparison between the different precursor solutions in otherwise identical
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18 conditions have been done. In particular, the role of both the solvent and the salts for the
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20 morphological, optical and electrical properties of the deposited films has been
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22 investigated.
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32 **Experimental**

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36 The spray deposition was carried out in a custom built confined environment (Abbess
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38 18" Cube), employing an air blast atomizer nozzle (PNR Air assisted ultrasonic atomizer,
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40 model MAD 0331 B1BA) placed at a distance of 29 cm from the deposition substrate.
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42 Air was used as carrier gas and a mass flow controller (Vögtlin, model red-y) was used to
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44 regulate the flow. The oxygen concentration inside the chamber was monitored using an
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46 oxygen sensor (Sensortech, model XYA1) placed at a distance of 35 cm away from
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48 the nozzle. The substrate consists of glass slide (Fisher brand, thickness 0.8-1mm) kept at
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50 a constant temperature through a ceramic heater (Watlow model CER-1-01-00007). For
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52 the liquid delivery a peristaltic pump (Watson Marlow Pumps Peristaltic 520S) has been
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6 In order to find out the most suitable decomposition temperature for each precursor,
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8 this was varied from 573 to 723 K, with steps of 50 degrees. For the sake of simplicity
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10 the temperatures reported are the ones referred to the heater set point. However, in order
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12 to measure the thermal gradient across the glass slide and cooling power due to the air
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14 stream and the spray solvents, a type K thermocouple (nickel-chromium) was placed in
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16 test experiments within 1 mm above the glass surface, in a region where the reaction is
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18 expected to happen. For the actual sample growth this was removed to have an
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20 unobstructed sample surface.
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25 For the synthesis, all the chemicals were purchased from Sigma-Aldrich and used
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27 without any further purification. The solvents employed were methanol, ethanol, both
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29 HPLC-grade, and deionised water. For selected samples, a mixture of them was used. For
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31 the ZnO synthesis, $\text{Zn}(\text{CH}_3\text{CO}_2)_2 \cdot 2\text{H}_2\text{O}$, $\text{Zn}(\text{NO}_3)_2 \cdot 6\text{H}_2\text{O}$, and ZnCl_2 were used as Zn
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33 source. In all cases a 0.2 M solution was used.
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36 The following precursor solutions have been used for sample growth.

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38 Zinc acetate was employed both with water, methanol and a mixture of
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40 ethanol/methanol equal to 70/30. The use of this has been necessary in order to speed up
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42 the dissolving process. Moreover in order to test the influence of water as solvent,
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44 mixtures with a ratio $\text{CH}_3\text{OH}/\text{H}_2\text{O}$ equal to 75/25, 50/50, 25/75 have been tested as well.
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48 The ZnCl_2 precursor was employed either with water, methanol and ethanol, as well as
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50 in a mixture of $\text{H}_2\text{O}/\text{CH}_3\text{CH}_2\text{OH}$.
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53 The $\text{Zn}(\text{NO}_3)_2 \cdot 6\text{H}_2\text{O}$ precursor was used just in full methanol, based on the results for
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55 the other precursors.
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3 For all the synthesis the liquid flow rate was fixed to 2.66 ml min^{-1} , the gas flow was
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6 14 l min^{-1} . The best decomposition temperature was 623 K for the acetate and nitrate
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8 precursors while for the chloride the decomposition temperature was 673 K.
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10 Doping has been carried out employing $\text{Mg}(\text{CH}_3\text{CO}_2)_2 \cdot 4\text{H}_2\text{O}$ and $\text{MgCl}_2 \cdot 6\text{H}_2\text{O}$ as
11
12 magnesium source, $\text{AlCl}_3 \cdot 9\text{H}_2\text{O}$ and $\text{Al}(\text{NO}_3)_3 \cdot 9\text{H}_2\text{O}$ and $\text{AlOCH}(\text{CH}_3)_{23}$ for aluminium.
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14 For the dissolution of the aluminium isopropoxide, a mixture of 70% isopropanol and
15
16 30% methanol has been used. The nominal molar concentration ratio of these doping
17
18 agents was $[\text{Mg}]/[\text{Zn}] = 10\%$ and $[\text{Al}]/[\text{Zn}] = 4\%$. These values have been chosen taking
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20 into consideration the data reported in literature ²⁶⁻³⁴. In order to find the optimum
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22 concentration, regarding film quality and conductance, we screened a larger range of
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24 Al/Zn and Mg/Zn ratios. For the scope of this paper we hence focus on the already
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26 optimized values. Due to the small fraction of doping agent present, all other parameters
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28 were kept as reported above for the undoped ZnO.
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34 The crystallographic analysis was made by X-ray diffraction (XRD) employing a
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36 Bruker D8 Discovery (Bragg Brentano configuration, Cu-tube, Göbel mirror, 0.2 mm
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38 horizontal entry slit, 4.5 mm soller entry slit, 2.5mm soller exit slit, horizontal exit slit via
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40 a LynxEye stripe detector (0.075 mm)). The resulting XRD patterns were analyzed by
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42 carrying out a numerical reconstruction of line profiles according to the Rietveld method.
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44 For this purpose, the MAUD software was employed
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48 The morphological analysis was carried out employing an atomic force microscope ,
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50 AFM, (NT-MDT SPM Solver PRO NT-MDT, tip NSC35/AIBS) or the optical
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52 microscope (Leitz Laborlux 12 ME with standard bright field and interference contrast
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54 capabilities, fitted with a Leica DFC420 Camera, PC controlled), depending on the
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3 roughness of the sample.
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5 The optical properties (transmission) were determined by a Cary 50 UV-Vis-NIR-
6 spectrophotometer equipped with a Xenon lamp.
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10 The electrical measurements have been carried out with conventional four point probe
11 method or a simple 2 wire method for low conducting samples (Agilent E3634A constant
12 current source at 2-5mA, Agilent 34401A multimeter) using gold capped spring loaded
13 contacts in a linear arrangement with pitch of 7.5mm).
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19 20 21 **Role of solvent** 22 23

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26 The role of solvent has been tested employing both zinc acetate and zinc chloride as
27 precursors. Using the organic precursor, the ZnO layer was obtained employing water,
28 methanol or a mixture of them. Several films have been grown changing the solvent
29 composition (ratio between water and methanol) as following: 100/0, 75/25, 50/50,
30 25/75, 0/100. All the other parameters were kept fixed. Despite the different solvent
31 composition, from the crystallographic point of view, all the samples consist of just one
32 phase, zincite (PDF number 01-074-0534), with hexagonal structure (Fig. 1). No traces of
33 unreacted precursors have been found (acetate: PDF-033-1464, chloride: PDF-01-072-
34 1285). The refinement carried out with MAUD indicates that the cell parameters are: a
35 $=3.246$, $c =5.258$ Å. The sample grown in pure methanol and the one with a solvent
36 composition containing 25% of water show dominantly (002) oriented crystals, while for
37 all the others, a good fit can be obtained only assuming that the sample is composed of
38 different micro-crystallites, some of which have a (002) and others have (100) preferred
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5 The relationship between the morphology of the sample and the solvent composition is
6 straightforward. Smooth, good quality layer can be obtained just by using methanol as
7 solvent while the surface roughness gets with increasing water content (Fig. 2). The
8 morphology of the film has a direct influence on the optical properties of the coating
9 (Fig. 3). Increasing water content leads to a decrease in the transparency of the film. It is
10 worth noting that also the growth rate increases with the water content. This has already
11 been observed in literature in the case of the SnO₂³⁵. Nevertheless the above mentioned
12 decrease in transmission is not caused by the thickness of the sample, but it is a
13 consequence of the scattering losses at the rough surface. Only the methanol grown film
14 is smooth enough to observe typical Fabry-Perot oscillations of thin transparent films. In
15 order to verify this, samples with a comparable thickness have been grown employing a
16 mixture of 50/50% water/methanol and 100% methanol. For this purpose, the growth
17 time has been shortened to account for the higher growth rate of the water-based solution
18 in comparison with the pure methanol one. For these layers of similar thickness the ones
19 grown with water are always rougher and hence show a lower transmission. Optical band
20 gap values as determined by linear extrapolation of the transmission data are found to be
21 unaffected by the choice of solvent and was found to be 3.35 ± 0.05 eV.
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46 In order to understand the major cause for the roughness, some basic parameters have
47 been monitored during the growth. As stated before, the droplet size and the temperature
48 of the surface play a crucial role for the growth of a good layer. With respect to the
49 particle size, it is easy to understand that solvent with a low density create droplets with
50 lower size, which don't impinge onto the surface. In this case the vaporization of the
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3 solvent happens just above the surface leading to a heterogeneous reaction ³⁵. Therefore,
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5 it can be argued that, for this particular type of nozzle, the lower density solvent creates
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7 droplets with smaller size and more homogeneous distribution, improving the
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9 performance of the process. Nevertheless, this is not the only role played by the solvent.
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11 In order to confirm this, three samples were grown using pure water, pure methanol and a
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13 mixture ethanol/methanol (70/30). For each sample the oxygen concentration in the
14
15 pyrolysis chamber has been monitored during the growth. The relative decrease in the
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17 oxygen concentration suggests that the solvent burns during the process (Fig. 4). In fact
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19 the oxygen concentration drops down for all of the three solvents used but, in the case of
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21 the organic solvent the decrease is much larger. In the water case the decrease is due to
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23 the change in chemical composition of the atmosphere inside the chamber as water
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25 vapour replaces air, while for the organic solvent the change is either due to the
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27 combustion products (mainly water and CO₂, even if the presence of the co-product
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29 cannot be excluded), due to solvent that doesn't burn and due to the oxygen consumption
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31 caused by the burning of the solvent. As the solvent burns mostly in the vicinity of the
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33 surface, the exothermic burning will provide additional heating to the salt decomposition.
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35 In order to confirm this hypothesis, the heater power supplied needed to keep its
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37 temperature constant, has been analyzed. To keep the heater at 423K during the
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39 deposition in the case of water, 63 W was needed, while in the case of methanol less
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41 power has been delivered (50 W). As the temperature within the heater is a function of
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43 cooling power of the sprayed solution and the thermal conductivity of the substrate, these
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45 results already show the importance of an active temperature control, as the reduction in
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47 surface temperature is partly compensated by the adjustment in heater power, leading to
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3 more reproducible surface temperatures. However, even with this active compensation,
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5 different solvent have shown different cooling rates which influence, to different extent,
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7 the actual surface temperature. To quantify these, a thermocouple has been attached to
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9 the glass slide surface and the heater has been set to a constant power value able to keep
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11 it at a similar temperature. In this way the effect of the closed loop system has been
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13 cancelled. Due to its position, the temperature monitored is relative to the layer of air just
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15 above the glass surface (within 1 mm), where the reaction is supposed to happen. The
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17 cooling power due to the air stream itself, the water spray and due to two organic solvents
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19 has been measured. The data revealed that the temperature above the glass slide is 651 K
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21 when the heater reading is 615 K. Due to the cooling caused by the air stream, the glass
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23 slide temperature drops down to 591 K. When the water is sprayed, the surface
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25 temperature decreases further to 573 K, while for methanol the temperature doesn't vary
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27 with respect the value measured for the air stream. In this case no precursor salt has been
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29 added to the solvent and therefore the properties measured are related just to the solvent
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31 used and hence universally applicable to any other pyrolysis growth process. It can be
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33 seen that the largest drop of surface temperature of ~60 K is caused by the air stream.
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35 Absolute values of this decrease are highly dependent on the heat capacity of the heater,
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37 and also the air pressure. For piezo-electric nebulizers this drop should be less significant
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39 due to the lower gas flow.
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48 Water has shown a greater cooling rate due to its evaporation (18 degrees), while the
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50 organic solvent burns, hence compensating the cooling. In fact considering the enthalpy
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52 evaporation process for both the solvent ($\Delta_{\text{ev}}H(\text{H}_2\text{O}) = 40 \text{ kJ/mol}$, $\Delta_{\text{ev}}H(\text{CH}_3\text{OH}) = 35$
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54 kJ/mol) and the respective sprayed moles (0.15 for water and 0.067 for methanol), the
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3 drop in temperature for methanol should be roughly half of the water one. In other words,
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5 assuming a drop in temperature of 18 degrees for water, the expected value for methanol
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7 should be 8 degrees. The fact that no temperature drop was observed can be explained if
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9 we accept that the methanol burns in the process thus releasing energy. If the heater
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11 temperature is controlled by a closed loop system, the drop caused by the air blow or
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13 water sprayed is lower compared to the open loop (50 K vs 60 K for air and 15 vs 18 for
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15 water). The reason is that the heat loss due to air/water is partially compensated by
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17 increased power of the heater. Within the error of our measurement no difference in
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19 either oxygen concentration or surface temperature has been found between methanol and
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21 ethanol. This can be explained only if the burning of the ethanol is incomplete. In fact the
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23 standard enthalpy of combustion of ethanol and the relative oxygen consumption are
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25 higher than for methanol. Nevertheless, the calculation of the overall quantity of oxygen
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27 inside the chamber shows that this is not enough to completely burn the solvent sprayed.
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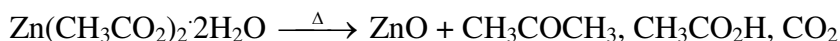
34 Although direct temperature measurements have been performed only with pure
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36 solvents, our indirect measurements (required heater power and oxygen consumption),
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38 carried out during deposition, show that these effects are generically applicable for
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40 solutions including different precursor salts. In fact, when the same tests have been
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42 repeated for the chloride precursor, higher power consumption and lower oxygen
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44 depletion have been observed for water than for the organic solvent. Again, no significant
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46 differences in heater power and oxygen concentration between methanol and ethanol
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48 solutions have been observed. The general nature of this behavior can be explained as the
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50 low quantity of salt present in the solution (~0.2M) does not significantly alter the solvent
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52 burning process. However, absolute values may differ due to different spray rates,
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3 temperature or even initial conditions of the growth atmosphere.
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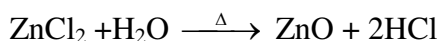
7 8 **Role of the precursor salt** 9

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12 As stated before, smooth, good quality layer can be obtain by using zinc acetate in
13 methanol. In contrast using zinc chloride led to rough discontinued layers, either in
14 combination with organic solvents, water or a mixture of them. We relate this to different
15 co-products that are formed during the pyrolytic decomposition of the two different
16 precursors.
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25 If zinc acetate is used, the pyrolytic decomposition leads to the formation of zinc oxide
26 according to the following reaction:
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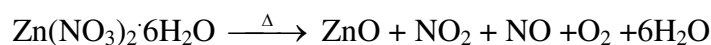
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32 The thermal decomposition of this precursor has been studied in literature using the
33 thermal gravimetric analysis (TG) coupled to the differential thermal analysis (DTA) ³⁶.
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35 The results show that the organic chain undergoes a series of reactions that ends up with
36 the production of volatile molecule, such as acetone, acetic acid and carbon dioxide),
37 while the zinc ions react with the oxygen present in the atmosphere or in the water to
38 form the correspondent oxide. This is deposited as a thin film onto the glass slide. The
39 chloride decomposition instead, leads to the formation of HCl as co-product according to
40 the following reaction:
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53 The poor surface morphology of the films grown using ZnCl_2 can thus be attributed to
54 the presence of HCl, which induced a chemical etching of the surface, leading to a rough,
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3 not closed film (Fig 5). This explanation is supported by the detection of the zinc chloride
4 hydroxide phase, (ZnClOH, PDF n 01-072-0525, Fig. 6) in the sample grown employing
5 a mixture of ethanol-water solution at 623 K. According to the TG-DTA studies reported
6 in literature ³⁷, the decomposition of this oxy-chloride is a complex process that involves
7 different pathways and intermediates, that ends with the formation of the hydrochloric
8 acid and zinc oxide. Therefore it can be concluded that the decomposition of the
9 precursor actually occurs, but, the intimate contact between the acid and the oxide leads
10 to the degradation of the latter one.
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22 The same reason can be advocated to explain the roughness of the film obtained by
23 using zinc nitrate as precursor (PDF-25-1231 ,Fig. 7). In this case the overall reaction is:
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28 Nevertheless, the TG-DTA studies reported in literature ^{38,39}, established that the thermal
29 decomposition of the $\text{Zn}(\text{NO}_3)_2 \cdot 6\text{H}_2\text{O}$ is again a complex process, for which different
30 pathways are available. In particular the decomposition of the nitrate fraction can occur
31 directly with the formation of the nitrogen oxides species (NO_2 and NO) or can involve
32 the formation of many different hydroxide species as intermediates, leading to the
33 formation of nitric acid as intermediate and its further decomposition. According to other
34 authors, the decomposition pathway of these species is temperature dependent, and for
35 intermediate values, the formation of HNO_3 has been confirmed. At higher temperatures,
36 the direct decomposition represents the main reaction. So, even if the temperature for the
37 decomposition of this compound has been set in the latter range, it is worth noting that
38 while the precursors are carried towards the substrate, they experience a thermal gradient
39 which may lead to the formation of the corresponding acid. Thus, it can be argued that
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3 the same basic explanation carried out to justify the chemical behavior of the chloride
4 precursor, can be extended also to the nitrate one. In other words, the formation of a
5 strong acid as intermediate or final product of the pyrolytic reaction leads to the
6 degradation of the film which thus results in a high roughness. We have shown here, that
7 for ZnO growth this etching process is limiting the quality of pyrolysis grown films.
8 Although the acid formation is a generic problem when chlorides and nitrates are used,
9 the actual impact for a given oxide can be quite different as it depends on the stability of
10 the oxide with respect to HCl and HNO₃. The etching process can have a significant
11 impact not only to the morphology but also the growth rate itself and even texturing, if
12 there are different etching rates for different crystallographic faces.
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27 In order to confirm the general nature of the problem of acid formation for the ZnO
28 growth, a doping study of the films has been done employing different precursors as the
29 cation source. If this is a generic problem, poorer films are expected whenever inorganic
30 salts were used as doping agent. In fact, in the case of significant Mg doping (10%), no
31 closed film can be obtain if chloride salts have been used as zinc and magnesium source,
32 while closed films have been obtained if zinc acetate was used. In this case, doping has
33 been made both with chloride and acetate as magnesium source. Even the relatively small
34 amount of MgCl₂ already leads to a degradation of film quality and a higher transparency
35 is obtained for the organic precursor (Fig. 8). The rougher sample due to the etching
36 process from HCl formed with the MgCl₂ precursor has a lower UV transmission due to
37 the enhanced scattering losses. Introducing Mg into the ZnO lattice does affect the optical
38 band gap, which was found to be 3.42 ± 0.05 eV.
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55 The same approach has been adopted for the Al doping. In this case the nitrate, the
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3 chloride and an organic precursor have been tested. As in the previous case, when the
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5 chloride or nitrate precursors were used, the film was rough and less transparent. If the
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7 organic precursor was used, smooth and highly transparent films were obtained (Fig. 9).
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9 In this case significant variation in the optical band gap determined by the transmission
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11 measurements occurred. The values if the aluminium isopropoxide is used is 3.36 ± 0.05
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13 eV, while for the nitrate and chloride 3.4 ± 0.1 eV and 3.45 ± 0.1 eV are measured.
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15 However it is not clear whether these changes are systematic errors in the determination
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17 for the rough, cracked films, differences in the actual aluminium incorporation or an
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19 actual influence of the precursor on the band structure of the material. Further
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21 investigations are required to clarify that finding.
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30 **Influence of the precursor on electrical properties**

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34 We have shown so far that the choice of solvent influences the morphology and
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36 optical properties of the film through the droplet size distribution, and also change in the
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38 surface temperature due to the solvent burning. Secondly we have shown that acid
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40 formation from inorganic salts in the reactive atmosphere increases surface roughness
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42 and hence decreases transmission. As aluminium-doped ZnO is used as transparent
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44 conducting oxide, we also wanted to test the influence of the Al-precursor salt on the
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46 electrical properties.
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51 All the ZnO:Al films have been grown in methanol with zinc acetate as zinc precursor.
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53 They showed a sheet resistance (R_{sh}), in the $M\Omega$ region. Films using aluminium chloride
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55 and aluminium isopropoxide showed sheet resistances of 1.5 and 1 $M\Omega/\square$ respectively,
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3 films with aluminium nitrate showed a sheet resistance of 21.5 MΩ/□. As the growth
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5 rates and hence film thickness varied, the resistivity (ρ) of the film has been calculated by
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7 normalizing the sheet resistance with respect to the measured thickness of the sample (t),
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9 according to the following relationship:
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$$R_{sh} = \rho/t$$

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15 The thickness value has been determined by a least square fit of the measured
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17 transmittance, using an optical multilayer model and published optical constants for ZnO
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19 ⁴⁰, and simply by the slide weight. The values determined optically for the sample
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21 obtained with the organic, nitrate and chloride precursors are 340, 185 and 165 nm,
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23 respectively, while the values determined through the weight are: 300, 280 and 230 nm.
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25 As it can be seen, a good agreement is settled between the two estimations in the case of
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27 the organic precursor, while the optical evaluation underestimated the thickness of the
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29 sample for the two inorganic precursors. This has to be attributed again to the roughness
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31 of the latter two samples that tends to dampen the Fabry-Perot oscillation. Considering
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33 the optical thickness, the resistivities are: 34 Ωcm⁻¹, 400 Ωcm⁻¹ and 25 Ωcm⁻¹
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35 respectively for the isopropoxide, nitrate and chloride aluminium precursor. So it can be
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37 seen that the chloride and organic precursor lead to a resistivity in the same order of
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39 magnitude. In case of the chloride, the value is underestimated due to the systematic error
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41 in the optical thickness evaluation of the rough sample. The nitrate is significantly worse
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43 by one order of magnitude. Obviously the choice of precursor influences not only the
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45 morphology of the film, and thus its optical properties, but also the electrical ones. In
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47 order to determine potential differences in the conduction mechanism, temperature
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49 dependent measurements have been performed in a range from 50-100°C. The
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3 conductivity is proportional to the number of carriers (n) and their mobility (μ) according
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5 to the following relationship ⁴¹:
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$$\sigma = q(\mu_n n_d + \mu_h n_a)$$

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15 Where μ_n and μ_h are the electron and hole mobilities and n_d and n_a the electron (donor)
16 and hole (acceptor) numbers. For the dominantly n-type ZnO films presented here,
17 however, the contribution of the minority carrier to the conductance can be neglected.
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22 With a nominal Al content of 4% it is reasonable to assume that not all donors are
23 thermalised at room temperature. The increase in conductance is then dominated by the
24 increase in thermally excited carriers following an exponential dependence:
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$$n_d \sim \exp(-E_d/k_b T)$$

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36 It is worth noting that E_a is related to the donor binding energy through the following
37 expression: $E_a = \frac{1}{2}(E_c - E_d)$, provided that E_c is the acceptor level of the conduction band
38 and E_d the donor level. Hence from a linear fit in an Arrhenius plot of the conductance
39 vs. temperature measurements (Figure 10), the activation energy E_a and hence the donor
40 binding energy can be extracted, assuming that there is a negligible temperature effect on
41 the mobility itself. The activation energies determined are 16 meV for the organic
42 precursor, 33 meV for the nitrate precursor and 20 meV for the chloride one. The latter
43 once are in agreement with previously reported donor binding energies ($E_c - E_d$) of the Al
44 donor of 53-65 meV ^{42,43}. The better conductance of the film grown with the organic
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3 precursors is supposed to originate from the significantly lower donor binding energy.
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5 Further studies are required to confirm this explanation and to identify the donor. It is
6
7 likely that the presence of reactive hydrogen or possibly carbon leads to the formation of
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9 Al-H, Al-C, Zn-H, Zn-C, O-H or O-C defect complexes, leading to a different donor
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11 level^{42, 43}.
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15 Unfortunately the determination of activation energies via resistance measurements alone
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17 is not enough to verify this hypothesis as there is the possibility that despite the high
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19 doping levels all carriers are already thermalised and the exponential dependence of the
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21 conductance with temperature arises from a grain boundary scattering limited transport.
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23 In this case the dependence of the carrier concentration with the temperature is negligible,
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25 while the mobility of the carriers varies with temperature as ⁴⁴:
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$$\mu = \mu_0(T)^{1/2} \exp(-E_b/k_B T)$$

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36 E_b represents the thermal activation energy of the scattering process through the grain
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38 boundary. Assuming that changes in the term $\mu_0(T)^{1/2}$ are small in comparison with the
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40 exponential term over the temperature range measured (323 to 373 K), the linear fit
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42 Arrhenius plot (Figure 10) would provide an estimate of this barrier. It is possible that
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44 since the films grown with aluminium isopropoxide are significantly smoother than those
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46 grown with aluminium chloride or nitrate, the microscopic structure of the grain
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48 boundaries varies. In addition less grain boundaries and hence a higher conductance are
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50 expected, however the slope of the curve should only change if also the microstructure of
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52 the boundaries is significantly changed.
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3 In both cases the higher resistance for the nitrate precursor (in comparison to the
4 chloride) can be directly correlated to a reduced number of carriers. Further analyses are
5 required to identify the reason for that, but one of the hypotheses can be the actual
6 incorporation of the oxygen created by the decomposition of the nitrate moiety inside the
7 grain boundaries.
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11 To conclude, the discussion reported so far shows that the choice of precursor salt for
12 the dopant, influences not only the morphology as described above but also the
13 conductance. In fact, the effective number of incorporated dopants might change with the
14 type of salt, as well as the type of donor, possibly due to the formation of defect
15 complexes including other elements in the precursor such as hydrogen and carbon in the
16 case of organic precursors. Alternatively the microstructure of grain boundaries is
17 modified. With the present data both models or a combination of them are possible, and
18 direct measurements of carrier concentration and mobility over a wider temperature range
19 (in particular at low temperatures), as well as quantitative measurements of the
20 aluminium content would be required to distinguish them.
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41 **Conclusion**

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45 A systematic study on the influences of different solvents and precursor salts on the
46 performance of the spray pyrolytic process of ZnO and ZnO:Al has been presented. In
47 particular the role of the solvent has been correlated to the optical properties of the layers
48 deposited. A correlation between the physical and chemical properties of the solvent, the
49 type of nozzle used and the quality of the layer has been established. Summarizing, when
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3 relative simple air blast nozzles are used, a low density, volatile solvent is required in
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5 order to get smaller droplets size and favour the evaporation of the solvent itself.
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7 Moreover, the burning of the organic solvent during the deposition has been
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9 demonstrated. It has been established that this process can actually compensate the
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11 cooling power of the liquid in itself, affecting one of the most important parameters of the
12
13 entire process: the actual temperature at which the reaction occurs.
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17 The role of the precursor salt has been systematically investigated with three different
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19 types of precursor, namely the nitrate, the chloride and an organic one (isopropoxide for
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21 Al, acetate for Mg and Zn). For all the three cations, the best results have been achieved
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23 employing the organic salt. The reason for this can be ascribed to the decomposition of
24
25 the organic moiety which leads to the formation of volatile, inert products. Instead, the
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27 anion moiety decomposition can lead to the formation of strong acids as intermediate or
28
29 final products, and higher film roughness have been observed. This has been attributed to
30
31 the chemical etching that these acid species induce. The roughness so created, determines
32
33 a degradation of the optical properties of the compound. Secondly, the choice of doping
34
35 precursor salt can influence the type of carrier responsible for the electrical properties
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37 (via the formation of different defect complexes), their concentration (due to differences
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39 precursor decomposition rate) and possibly variations in the grain boundary
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41 microstructure (different overall morphology).
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50 **Acknowledgment**

51
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4 Figure 1: XRD patterns of ZnO samples grown with zinc acetate in varying solvent
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6 composition. The corresponding composition water/methanol ratios are A: 100/0, B:
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8 75/25, C: 50/50, D: 25/75, E: 0/100. The main peaks relative to the zincite phase are
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10 indicated.

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15 Figure 2: Morphology of the samples grown with different solvent composition.
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17 Images A-D have been taken with an optical microscope, while E is an AFM picture. The
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19 bar in the optical images stands for 500 μm . The corresponding composition
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21 water/methanol ratios are A: 100/0, B: 75/25, C: 50/50, D: 25/75. Sample E grown in
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23 pure methanol had no visible contrast in the optical microscope and an AFM image is
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25 shown instead. It is clear that size and number of large circular crater caused by the
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27 impact of the largest unevaporated droplets are significantly reduced with increasing
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29 methanol content.
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37 Figure 3: Transmission measurements of samples grown with varying solvent
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39 composition. From the bottom to the top, the ratio water/methanol is 100/0, 75/25, 50/50,
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41 25/75, 0/100.
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47 Figure 4: Oxygen concentrations as a function of the growth time for water (dotted),
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49 methanol (solid) and a mixture ethanol/methanol (70/30, dashed) as solvent. The more
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51 significant drop in the case of organic solvents is caused by the oxygen consumption due
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53 to burning.
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3 Figure 5: Morphology of the ZnO samples grown employing zinc chloride as
4 precursor. The red bar equals 500 μm .
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10 Figure 6: XRD patterns of the sample grown employing a mixture ethanol/water
11 (70/30) as solvent and zinc chloride as precursor. The peaks are relative to the phase
12 ZnClOH.
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18 Figure 7 Optical microscope image referred to the ZnO sample grown employing
19 zinc nitrate as precursor. The bar equals 500 μm
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26 Figure 8: Transmission measurements of ZnO:Mg samples. The solid curve refers to
27 the sample where magnesium acetate was used, while the dotted one is the sample where
28 magnesium chloride was used.
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35 Figure 9: Transmission measurement of ZnO:Al samples grown employing aluminium
36 isopropoxide (dotted curve) , aluminium nitrate (dashed one) and aluminium chloride
37 (solid one) as source
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45 Figure 10: Conductance data as a function of the inverse of temperature. Samples have
46 been grown with different aluminium sources: (—) aluminium isopropoxide, (8)
47 aluminium chloride, and (∇) aluminium nitrate. The slopes (least square fits shown) give
48 the thermal activation energy for the main carrier of 34, 61, 66 meV respectively.
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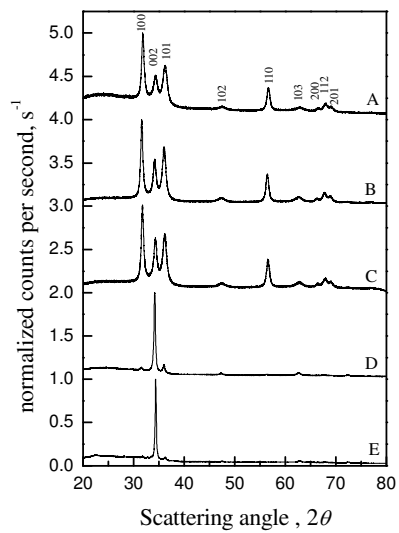


Fig 1

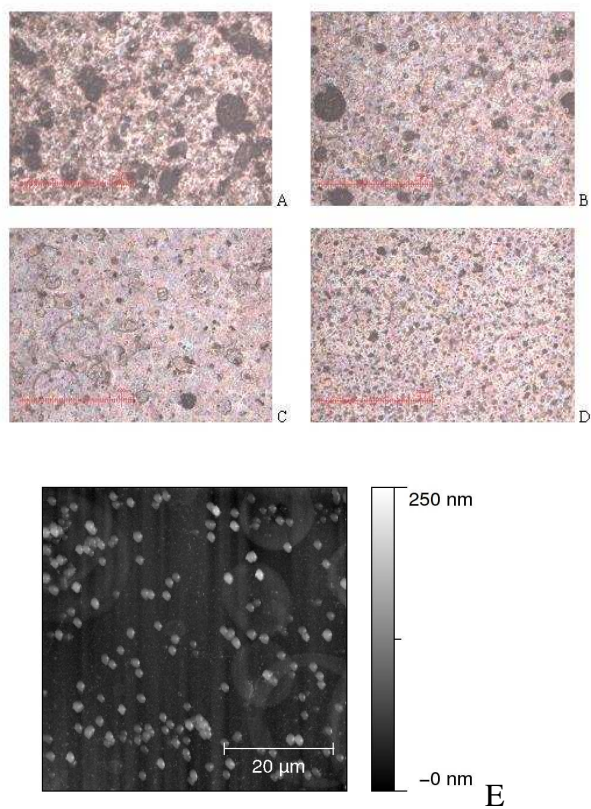


Fig 2

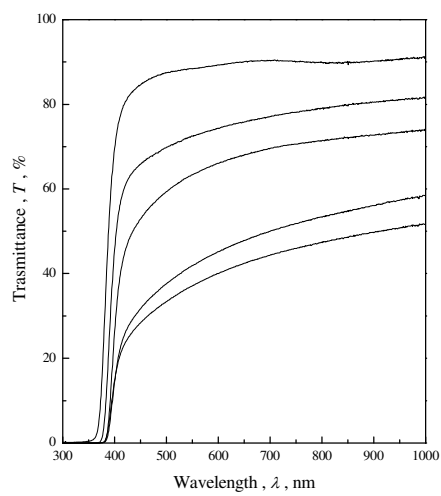


Fig 3

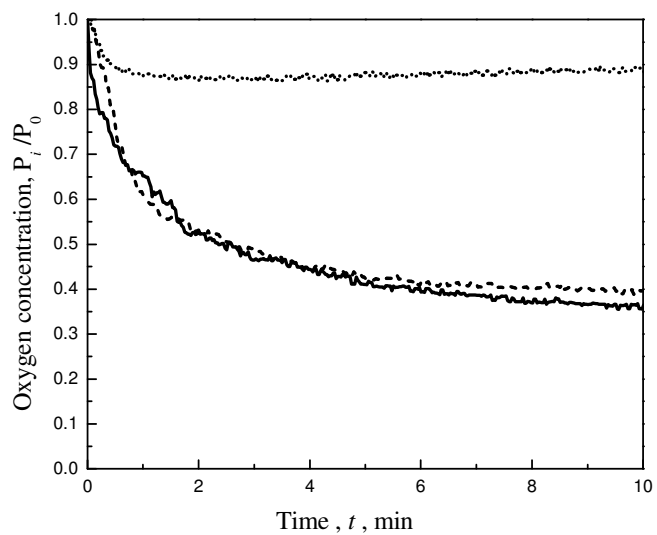


Fig 4

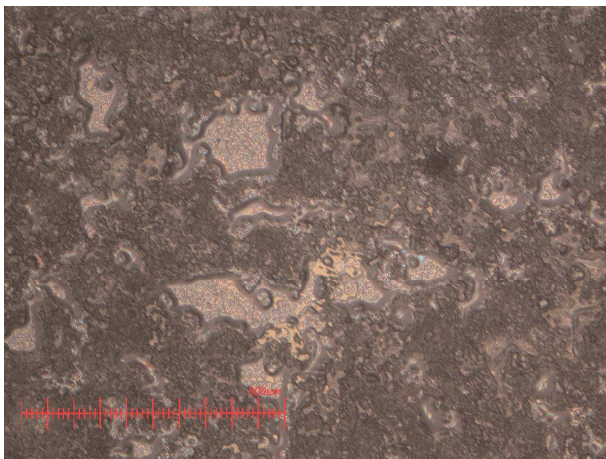


Fig 5

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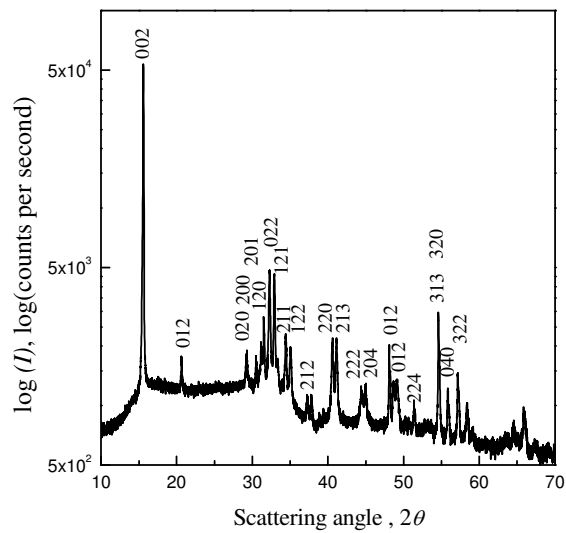


Fig 6

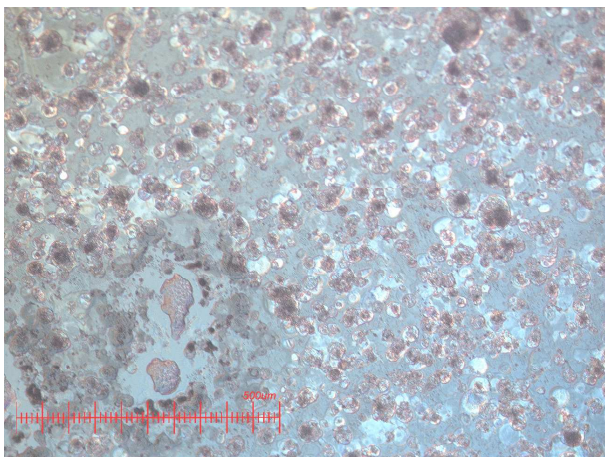


Fig 7

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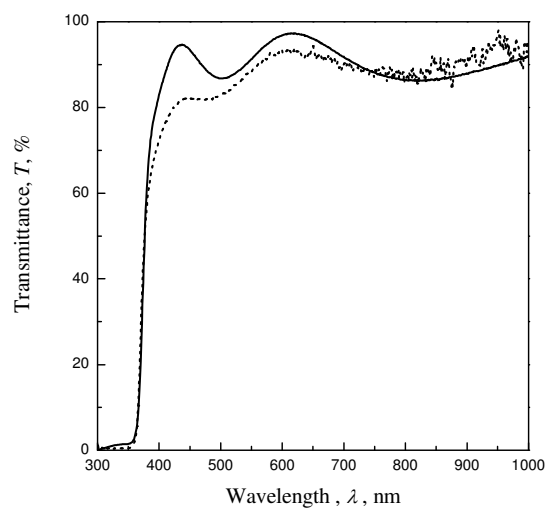


Fig 8

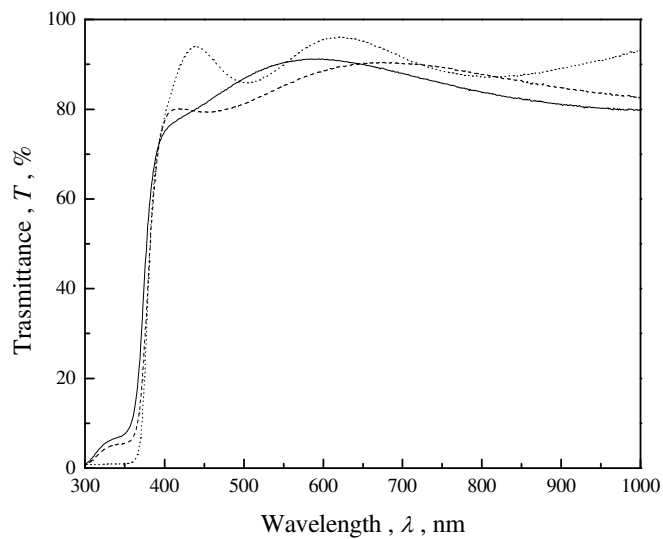


Fig 9

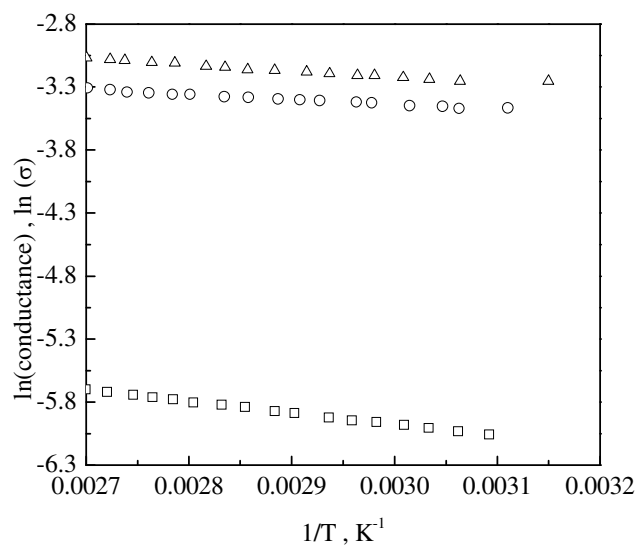


Fig 10

